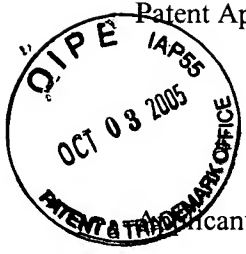


IFW



Patent Application 10/823,149

Docket No. TS01/195CC (24061.579)  
Customer No. 42717

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Lain-Jong Li, et al. §  
Serial No.: 10/823,149 §  
Filed: April 13, 2004 §  
For: Composite Etching Step in §  
Semiconductor Process Integration §

Docket No.: TS01-195CC (24061.579)  
Examiner: David Nhu  
Art Unit: 2818  
Conf. No.: 4561

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents  
Mail Stop: Amendment  
PO Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

The present paper is being submitted in response to the Restriction Requirement Office Action dated September 12, 2005 in the above-identified application.

**Election of Claims** begins on page 2 of this paper.

**Amendments to the Claims** are reflected in the Listing of Claims which begins on page 3 of this paper.

**Remarks** begin on page 6 of this paper.

**I. Election**

In the Office Action mailed September 12, 2005, the Examiner alleges that the application contains claims directed to two inventions and, thus, required restriction of either:

Group I: Claim 1, drawn to a method of fabricating an integrated circuit device; or

Group II: Claims 27-46, drawn to an integrated circuit device.

In response, Applicants hereby elect Group II, corresponding to claims 27-46. Applicants' election is made with traverse on the grounds that the embodiments delineated by the Examiner are not patentably distinct and therefore constitute a single invention concept.